2022년 1월 26일(수), 09:00-10:30

Room B (에메랄드 II+III, 5층)

D. Thin Film Process Technology 분과
[WB1-D] Two-dimensional Materials

좌장: 김성근 책임(KIST), 안지훈 교수(한양대학교)

WB1-D-1 **09:00-09:30**	**Heterojunction Band Engineering for vdW Electronics & Optoelectronics** Chul-Ho Lee[1,2] *[1]KU-KIST Graduate School of Converging Science and Technology, Korea University* *[2]Department of Integrative Energy Engineering, Korea University*
WB1-D-2 **09:30-09:45**	**Wafer-scale Crystalline MoS_2 Thin Films with Controlled Morphology Using Pulsed Metal-organic Chemical Vapor Deposition at Low Temperature** Jeong-Hun Choi, Min-Ji Ha, and Ji-Hoon Ahn *Department of Materials Science and Chemical Engineering, Hanyang University*
WB1-D-3 **09:45-10:00**	**Two-dimensional Electron Gas for Conductive Bridge Random Access Memory** Ju Young Sung[1,2], Chang Hee Ko[1,2], Chae Hyun Lee[1,2], Tae Jun Seok[3,4], Ji Hyeon Choi[3,4], Tae Joo Park[3,4], and Sang Woon Lee[1,2] *[1]Department of Energy Systems Research, Ajou University, [2]Department of Physics, Ajou University, [3]Department of Materials Science & Chemical Engineering, Hanyang University, [4]Department of Advanced Materials Engineering, Hanyang University*
WB1-D-4 **10:00-10:15**	**Two-Step Atomic-Layer-Deposited $GeSe_2$ for High-Performance Ovonic Threshold Switch** Woohyun Kim[1], Chanyoung Yoo[1], Jeong Woo Jeon[1], Wonho Choi[1], Byongwoo Park[1], Gwang Sik Jeon[1], Sangmin Jeon[1], Yoon Kyeung Lee[2], and Cheol Seong Hwang[1] *[1]Department of Materials Science and Engineering and Inter-University Semiconductor Research Center, Seoul National University, [2]Division of Advanced Materials Engineering, Jeonbuk National University*
WB1-D-5 **10:15-10:30**	**Temperature-Dependent Growth of Tin Selenide (Sn_xSe_{1-x}) Thin Films by Atomic Layer Deposition** Jeong Woo Jeon[1], Chanyoung Yoo[1], Woohyun Kim[1], Wonho Choi[1], Byongwoo Park[1], Gwangsik Jeon[1], Sangmin Jeon[1], Yoon Kyeung Lee[2], and Cheol Seong Hwang[1] *[1]Department of Materials Science and Engineering and Inter-University Semiconductor Research Center, Seoul National University, [2]Division of Advanced Materials Engineering, Jeonbuk National University*